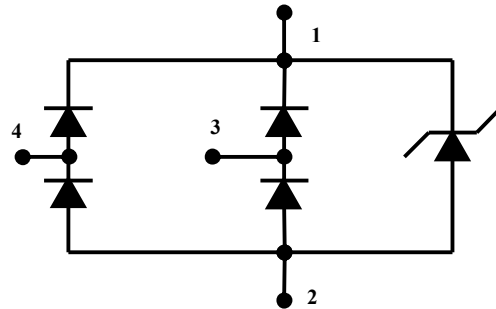
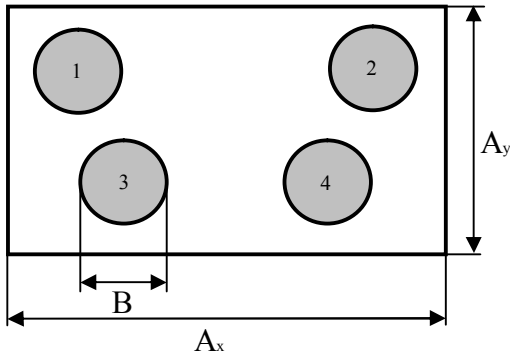


Chip for Low Capacitance 2-Line ESD protection in wafer form, 4 inch.



Schematic and pinning diagram.

Mechanical data: $A_x=630\mu\text{m}$, $A_y=330\mu\text{m}$, $B=80\mu\text{m}$

Thickness: a) $138\pm 12\mu\text{m}$; b) max. $450\mu\text{m}$ without grinding.

Scribe Line width - $60\mu\text{m}$.

Top Metal: Al - for wire bonding, $d=4.0\pm 0.4\ \mu\text{m}$.

Back Metal: a) Ti-Ni-Ag; b) without metallization.

Probing: a) **sampling testing:** no bad dice inking;

guaranteed good dice quantity $\geq 93\%$.

b) **100% testing (if agreed with customer):** wafer mapping data;
no bad dice inking.

Limiting values

Parameter	Symbol	Conditions	Value	Unit
Reverse Stand-off voltage	V_{RWM}	-	5,5	V
Peak Pulse Power	P_{pp}	$t_p=8/20\mu\text{s}$	80*	W
Peak Pulse Current	I_{pp}	$t_p=8/20\mu\text{s}$	4*	A
Electrostatic Discharge, all pins	V_{ESD}	IEC 61000-4-2, level 4. Contact.	± 8	kV
Max.junction temperature	T_j	-	+125	$^{\circ}\text{C}$

Characteristics ($T_j=25^{\circ}\text{C}$)

SYMBOL	PARAMETER	CONDITIONS	MIN.	TYP.	MAX.	UNIT
V_{BR}	Reverse breakdown voltage. Pins 3, 4 to 2	$I_R=1\text{mA}$	6.1	7.0	8.5	V
I_R	Reverse leakage current. Pins 3, 4 to 2	$V=+5\text{V}$	-	-	0.8	μA
V_F	Forward voltage	$I_F=1\text{mA}$	-	-	0.9	V
V_{CL}	Clamping Voltage	$I_{pp}=1\text{A}$, $t_p=8/20\mu\text{s}$ $I_{pp}=4\text{A}$, $t_p=8/20\mu\text{s}$	-	-	12* 20*	V
$C_{I/O}$	Pin capacitance. Pins 3, 4 to 2.	$V_R=0\text{V}$, $f=1\ \text{MHz}$	-	-	0.8	pF
$C_{I/O-I/O}$	Capacitance pin 3 to pin 4.	$V_R=0\text{V}$, $f=1\ \text{MHz}$	-	0.4	-	pF

*For Device testing.